A study of partially irreversible characteristics in a TTF–TCNQ gas sensing system

Jung-Yu Liaoa, Kuo-Chuan Hoa,b,*

a Department of Chemical Engineering, National Taiwan University, Taipei 10617, Taiwan
b Institute of Polymer Science and Engineering, National Taiwan University, Taipei 10617, Taiwan

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Abstract

The irreversible gas sensing behavior is investigated for TTF–TCNQ complex in the presence of NO2 or O2. Reactions with the gas molecules are the main reason to cause the irreversibility, which has been reported and supported by analytical data. The totally irreversible behavior was noticed when a TTF–TCNQ thin film was brought in contact with NO2 gas. As for O2 gas, however, only partially irreversible phenomenon was observed. For a TTF–TCNQ thin film that interacts with NO2 or O2 gas, the degree of irreversibility is determined by the competition ratio of the desorption rate to that of the reaction rate. A theory based on the competition concept was proposed and a general expression for three possible behaviors (totally reversible, totally irreversible, and partially reversible cases) in a gas sensing system was obtained. The O2 sensing data match the theoretical prediction when the reaction and the adsorption are limited at the surface.

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1. Introduction

Tetrathiafulvalene (TTF)–tetracyanoquinodimethane (TCNQ) complex is a highly conductive [1] organic material, and is found to be sensitive to several gas species, such as NO2, O2, CO2, etc. [2] Its individual components, TTF and TCNQ molecules and their individual derivatives, were reported to be ambient gas sensitive as well. There have been several discussions about how these materials are affected by the gases that surround them [3–8].

It is conceived that the structure of TTF [3] has been changed in IR spectrum (805–835 and 1270–1420 cm−1) during NOx exposure. The TTF derivative thin film [4] have been reported as well to become radical cation when dipping in iodine vapor. Hennion et al. [5] also reported that redox reaction, color change, as well as resistivity change can be observed when TCNQ-derived LB films were exposed to iodine gas. Perez et al. [6] discovered the change of charge transfer band of TCNQ derivative films under NO2 exposure. Hertler et al. [7] and Suchanski and Duyne [8] showed that TCNQ and TCNQ2− anion decomposed in the presence of NO2 and O2 gases.

Compare to the existing evidence for TTF, TCNQ and their individual derivatives, there are only limited information about the effect of ambient gases on the sensing properties of a TTF–TCNQ complex. For example, Jouve et al. [2] reported that a TTF–TCNQ complex containing a polymer film shows irreversibility in NO2 detection and partial reversibility in O2 and H2O detections. Based on the possible reactive nature of TTF–TCNQ complex, our previous work [9] had focused only on the irreversible sensing and modeling for NO2 detection. One of the objectives of this study is to find out the reaction mechanism for a TTF–TCNQ complex when exposing to NO2 or O2 gas. Another objective is to establish a general model (completely reversible, partially reversible for O2, and totally irreversible for NO2) for those sensing materials that might be reactive.

2. Experimental

TTF–TCNQ complex is obtained by dissolving both TTF (Fig. 1(a)) and TCNQ (Fig. 1(b)) powders (Aldrich, TTF:97%; TCNQ:98%) into acetonitrile to form a 1:1 molar ratio radical cation–radical anion pair complex, as a precipitate.
Fig. 1. The molecular structures of: (a) Tetrathiafulvalene, TTF; (b) Tetrayanoquinodimethane, TCNQ; (c) TTF–TCNQ complex.

(Fig. 1(c)). The preparation steps follow the procedure described in literature [1]. The complex powder is further purified by recrystallization in acetonitrile. Sensing thin film is thermally evaporated onto various substrates, including KBr (for FTIR), glass (for UV–vis, SEM and XRD), Pt coated quartz (for QCM), and Al2O3 with printed interdigitated gold electrode (for conductance) under 3 × 10−5 Torr vacuum. Film thicknesses are controlled at about 0.15–0.2 μm for both conductance and QCM measurements and 0.50–1.00 μm for other analytical experiments (XRD, UV–vis, FTIR and SEM). The deposition rate is ca. 5–10 Å/s.

The sensing film that face against the gas inlet at a flow rate of 200 ml/min is placed in a sensing chamber described elsewhere [9]. The sensing was carried out under room temperature. NO2 and O2 (from liquid air) gases are diluted with pure N2 that is inert in this system. Unless stated otherwise, the standard sensing (exposure) process for analytical experiments was carried out for at least 12 h with 500 ppm NO2 gas stream at 200 ml/min. The conductance was recorded by EG&G model 273A potentiostat/galvanostat. The QCM measurements were accomplished by Seiko EG&G QCA917, respectively. The UV–vis and FTIR spectra were carried out by Shimadzu UV-1601PC and Bio-rad FTS-40. The XRD and SEM data were obtained by Philips PW1710 (λ = 1.540 Å, scan rate = 3 deg/min) and Hitachi S-800, respectively. The detail experimental setup can be found in our previous work [9].

3. Results and discussions

3.1. Reaction involved sensing mechanism

In our previous work [9], a totally irreversible reaction is assumed in the model deduction. We are interested in finding the mechanism involving the conductive property and how the conductivity is affected. Several methods have been carried out to identify the possible reactions and conductive mechanisms.

3.1.1. Irreversible sensing response

Fig. 2(a) is a typical irreversible conductance response for NO2 detection using a TTF–TCNQ complex. First of all, thin film was pretreated for 1 h under N2 gas flow to ensure that moisture and other interfering impurities were totally removed. After approximately 43 h of 15 ppm NO2 exposure, pure and inert N2 gas was then purged again. However, it was found that the conductance does not recover when N2 purging was in action. Instead of monitoring the transient of the conductance, a mass detection was also carried out. The thin film and gas flow conditions employed to obtain the data in Fig. 2(b) are identical to that in Fig. 2(a), the only difference is that a quartz crystal microbalance (QCM) was used to record the mass transient. Although several fluctuations was found in Fig. 2(b) during the entire NO2 exposure process, one can notice an irreversible frequency decreasing (mass increase) trend which is consistent with the conductivity transient in Fig. 2(a).

After confirming the immobilization of NO2, as judged by the increasing mass and decreasing conductance of a TTF–TCNQ complex, two reasonable possibilities may be drawn regarding the incoming NO2 gas molecules, which are either “absorbed” within the film or “reacted” with the complex to form additional products and being immobilized inside the film.
3.1.2. Crystal structure

The standard X-ray diffraction (XRD) pattern with three characteristic peaks [10] representing different packing planes is shown in Fig. 3. The crystalline intensity is dramatically decreased when the exposure process is finished. This suggested that the penetration of NO2 molecules accompanied by reaction ruins the standard packing of this complex, hence lowering the intensity in the XRD pattern.

It is generally accepted that the distances between two parallel TTF and two parallel TCNQ molecules in the complex are about 3.47 and 3.17 Å [11], respectively. According to the kinetic theory of gas, the molecular diameter of a spherical molecule can be estimated by the viscosity of the gas [12]

\[ d^2 = \frac{2.67 \times 10^{-20} \times (MT)^{1/2}}{\eta} \]  \hspace{1cm} (1) 

where, \( d \) is the diameter of spherical molecule, \( M \) the molar mass, \( T \) the temperature in Kelvin, and \( \eta \) is the viscosity of the gas. Assuming that all molecules are spherical molecules and that the viscosities for N2, NO2 and O2 at 25 °C are 1.78 \times 10^{-5}, 1.32 \times 10^{-5} and 2.04 \times 10^{-5} (pa s), respectively [13]. Thus, the diameters calculated from Eq. (1) for N2, NO2 and O2 are 3.71, 4.87 and 3.58 Å, respectively, which are larger than the interplanar distance of TTF–TCNQ complex. It is highly unlikely that TTF–TCNQ complex itself will “absorb” the NO2 molecule and allow the gas to diffuse into the interplanar space which is relatively narrower. Since the immobilization was observed in either conductance or QCM measurement (as seen in Fig. 2), it indicates that the immobilization of gas molecules will bring the destruction of the standard packing of the complex, as evidenced in Fig. 3. If a real stick type (O2 and N2) or curvy molecular (NO2) shape is taken into account, the smoothly slip of molecules into the interplane becomes more difficult than a spherical one, and thus unlikely to happen.

3.1.3. Spectra analysis

Fig. 4(a) is the UV–vis spectra for a fresh and a NO2-exposed film samples dissolved in acetonitrile. It can be found that three absorption peaks, which represent TTF*+ (318 nm, may has been shifted from 340 nm) and TCNQ*- (743 and 838 nm, according to literatures [8,14–17], as summarized in Table 1) decrease after NO2 exposure. The major peak at 394 nm, which is due to the oxidation of TCNQ** to form TCNQ0 (both species absorb at 390–400 nm, referring to Table 1), still maintains its intensity after NO2 exposure. Minor absorption at 533 nm represents the formation of TTF**+. It has been reported that TCNQ0 molecule reacts with NO2 to form terephthaloyl cyanide [7] and TCNQ2− ion reacts with O2 to form DCTC− (~dicyano-p-toluoyl-cyanide) ion [8]. Both reactions are basically similar and are mainly involved in a side chain transformation (two sides for NO2 and one side for O2). The difference is mainly determined by the oxidizing capability resulting from the active radical’s existence in NO2 molecule.

Table 1

<table>
<thead>
<tr>
<th>Species</th>
<th>Peak ranges (nm)</th>
<th>References</th>
</tr>
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<tbody>
<tr>
<td>TCNQ**</td>
<td>400–455; 660; 728–760; 812–850</td>
<td>[14–16]</td>
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<tr>
<td>TCNQ0</td>
<td>390–412; 430–432</td>
<td>[14–16]</td>
</tr>
<tr>
<td>TTF**+</td>
<td>340; 393–405; 435; 575; 653</td>
<td>[16,17]</td>
</tr>
<tr>
<td>TTF2+</td>
<td>533</td>
<td>[16]</td>
</tr>
<tr>
<td>DCTC−</td>
<td>480</td>
<td>[8]</td>
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Therefore, it is believed that the minor peak at 480 nm in UV absorbance is due to the reaction with NO2 gas forming DCTC− (Table 1).

The FTIR spectra for the fresh and the NO2-exposed TTF–TCNQ thin films are shown in Fig. 4(b). The major absorption peaks (475, 860, 1354 and 1543 cm⁻¹, as summarized in Table 2) [18] found after NO2 exposure represent the formation of TCNQ0. Based on both UV and FTIR analyses, it is inferred that the major reaction involving TCNQ•− is

$$\text{NO}_2 + \text{TCNQ}^{-} \leftrightarrow \text{TCNQ}^{0} + \text{NO}_2^{-}, \quad \Delta G_2^0$$  \hspace{1cm} (2)

It is also reported that TTF0 is oxidized when exposing to NO2 with IR absorption region detected at 805–835 and 1270–1420 cm⁻¹ [3]. It is possible that the peak at 1377 cm⁻¹ is due to the oxidation of TTF•+, TTF2+ or their mixture [19]. Because the NO2-exposed film is yellowish in appearance, not deep purple (TTF•+) [17], it is suggested that TTF•+ is further oxidized to yellowish di-cation (TTF2+) in the actual reaction

$$\text{NO}_2 + \text{TTF}^{+} \leftrightarrow \text{TTF}^{2+} + \text{NO}_2^{-}, \quad \Delta G_3^0$$  \hspace{1cm} (3)

Since the bi-molecular exchanging from NO2 to N2O4 are left behind (TTF2+, TCNQ0, NO2), the remained porous product is called “tarnishing film” [9].

To summarize our previous discussion, a net reaction is proposed

$$2\text{NO}_2 + \text{TTF} - \text{TCNQ} \underset{k^\prime}{\rightarrow} \text{TTF}^{2+} + \text{TCNQ}^{0} + 2\text{NO}_2^{-} \quad (7)$$

This is to compare with the equation proposed in our previous work [9]

$$a\text{NO}_2(g) + \text{TTF} - \text{TCNQ}(s) \overset{k'}{\rightarrow} [(\text{NO}_2)_a - (\text{TTF} - \text{TCNQ})]_s \quad (8)$$

which can be denoted as

$$aB_{(g)} + A_{(s)} \overset{k}{\rightarrow} AB_{(s)} \quad (9)$$

where “a” is a stoichiometric factor between the reactants, which takes two NO2 molecules to react with both TTF•+ and TCNQ•−. B represents NO2, and A represents TTF–TCNQ complex, ABa may be viewed as the combination of the mixed three products listed in Eq. (7).

### 3.1.4. Hypothetical mechanism

As far as we know, NO2 does react with TTF–TCNQ complex, and it is reasonable to assume that the reaction is initiated by the strong interaction involving the unpaired electron (radical) located in the molecular orbital of NO2 and the radical cation–radical anion pair of TTF–TCNQ complex (Fig. 1(c)). It is possible that the unpaired electron of NO2 was attracted initially by the radical hopping through TTF–TCNQ complex packing. After the attracted NO2 reacted with the complex, the conductive route is interrupted, as evidenced by both the continuous decrease in the conductance (Fig. 2(a)) and the increase in the mass (decrease in frequency, Fig. 2(b)) during NO2 exposure.

Based on the well-known structure of the TTF–TCNQ complex [11], which possesses 1-D (y-direction) an-isotropic conduction [22] and our previous discussion, we propose a hypothetical mechanism, as depicted in Fig. 5, to visualize the interaction. In this mechanism, the highly conductive property of the complex is contributed by the “active” hopping radical provided by the TTF–TCNQ complex. The un-paired, highly reactive NO2 is attracted and reacted with the complex. The porous products are left behind (TTF2+, TCNQ0, NO2−), and small amount of

<table>
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<th>Species</th>
<th>Peak ranges (cm⁻¹)</th>
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<td>TCNQ0</td>
<td>3050; 2971; 2224; 1543; 1354; 1125; 1113; 862; 475</td>
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<tr>
<td>mixed</td>
<td>805–835; 1270–1420</td>
<td>[3]</td>
</tr>
<tr>
<td>NO2</td>
<td>1361; 1688; 770</td>
<td>[20]</td>
</tr>
<tr>
<td>NO2−</td>
<td>1325; 1270; 829</td>
<td>[20]</td>
</tr>
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</table>
Conductive Route without NO\textsubscript{2}

Route Interrupted by the Reaction with NO\textsubscript{2}

DCTC\textsuperscript{−}) and the conduction route is destroyed, while the un-reacted NO\textsubscript{2} keeps penetrating through the remains and react with the fresh complex.

3.1.5. Surface information from SEM

In the previous discussions, we imagine that the tarnishing film formed is a porous layer and allows larger molecules such as NO\textsubscript{2} to penetrate through. According to the SEM graphs shown in Fig. 6(a), which is the SEM image of a fresh TTF–TCNQ film coated onto a glass substrate, the surface of each chip of fresh TTF–TCNQ crystalline is quite smooth comparing to the NO\textsubscript{2}-exposed film in Fig. 6(b). The increase in surface roughness after NO\textsubscript{2} exposure supports the formation of a porous tarnishing film.

3.2. General modeling of TTF–TCNQ-based sensors

The TTF–TCNQ complex not only is sensitive to NO\textsubscript{2} but also sensitive to O\textsubscript{2}, as shown in Fig. 7. When exposing to O\textsubscript{2}, the transient conductance shows partially irreversible sensing characteristics for the TTF–TCNQ complex. This sensing behavior is different from that of NO\textsubscript{2}, as seen from Fig. 2(a). This means that the interaction between O\textsubscript{2} and TTF–TCNQ complex involves simultaneous adsorption/desorption and reaction processes.

In order to describe the partially irreversible behavior, the totally “irreversible reaction” model (proposed in our previous work [9]) and the totally “reversible adsorption/desorption” [23] model are adopted to form a general model.
The reactive gas, B

(ii) In this work, “A” represents TTF–TCNQ, which is assumed to offer two (TTF+ and TCNQ−) “identical sites (denoted as A’)” for the adsorption.

(iii) The reactive gas, B (e.g., O2 or any other oxidizing gas), behaves similarly to NO2 as seen in Eq. (7) with a stoichiometric factor of 2. Therefore, each site (A’) adsorbs only one gas molecule. Therefore, the general model, Eq. (11), can be simplified as

\[ B(g) + A' \xrightarrow[k_d']{k_a} A' - B(adsorbed) \xrightarrow[k_d']{k_a} A'B(reacted) \]  

The actual reaction may be proposed as

\[ 2O_2 + TTF - TCNQ \rightarrow TTF^{2+} + TCNQ^0 + 2O_2^- \]

where

\[ O_2 + e^- \leftrightarrow O_2^-, \quad E^0 = 0.56 \text{ V (versus NHE)} \]

The above reaction possesses less oxidizing capability than NO2 does in Eq. (4), as judged by the values of \( E^0 \).

(iv) The conductance (G) measured is proportional to the fresh site concentration of A’ (\( C_{A'} \)) which follows the reversible (semiconductor-type) kinetics concept (the adsorption of electron-drawing gases will localize the conducting radicals) [23], and

\[ G = P \times C_{A'} \]  

where P is a proportional constant.

(v) In order to quantify the partial irreversibility, the competition factor, \( f_c \), is defined as

\[ f_c = \frac{\text{desorption rate}}{\text{reaction rate}} = \frac{k_d C_{A-B}^0}{k' C_{A-A'}} = \frac{k_d}{k'} \]  

when \( f_c \gg 1 \) (or \( k_d \) is two orders higher than \( k' \), says \( f_c > 100 \)), the reaction term can be neglected, Eq. (11) is simplified to a purely reversible adsorption/desorption case, such as Eq. (10); and when \( f_c < 1 \) (or \( k_d \) is two orders smaller than \( k' \), says \( f_c < 0.01 \), the desorption term can be neglected), Eq. (11) is then simplified to a pure reaction case, as depicted in Eq. (9), and \( k_d = k' \) in this case.

When 0.01 < \( f_c < 100 \), the desorption and reaction processes are in competition with each other. Both desorption and reaction cannot be ignored and should be taken into account. The rate expressions for Eq. (11) are

\[ \frac{dC_{A'-B}}{dt} = k_d C_{B0} (C_{A'}^0 - C_{A'-B} - C_{A'B}) \]

\[ -k_d C_{A'-B} - k' C_{A'-B} \]  

\[ \frac{dC_{A'-B}}{dt} = k' C_{A'-B} \]  

where \( C_{B0} \) is the concentration of incoming gas B, which is a constant; \( C_{A'}^0 \) the initial surface site concentration of fresh site A’; \( C_{A'-B} \) is the surface concentration of adsorbed sites; \( C_{A'B} \) is the surface concentration of reacted sites; \( C_{A'} \) is the fresh site concentration (\( = C_{A'-B} - C_{A'B} \)); \( k_d \), \( k_d \), and \( k' \) are the adsorption, desorption, and reaction rate constants, respectively. The schematic expression for a competitive desorption/reaction model is shown in Fig. 8.

In order to solve Eqs. (14) and (15), two simplified forms are written as

\[ C_{1}' = -EC_1 - FC_2 + I \]

\[ C_{2}' = HC_1 \]
where \( C_1 = C_{A_1-B_1}, C_2 = C_{A_2-B}, E = (k_d C_{B0} + k_d + k'), F = k_d C_{B0}, I = k_a C_{B0} C_{A0}, H = k', C_{A0} \) and \( C_{B0} \) are constants. By assuming the initial conditions as \( C_1(t=0) = C_{10} \) and \( C_2(t=0) = C_{20} \), Eqs. (16) and (17) are solved by the Laplace transformation, and the solutions can be classified into two cases:

(a) Adsortion process (\( C_{B0} > 0 \))

\[
C_1 = C_{10} \exp \left( -\frac{E}{2} t \right) \cosh \left( \sqrt{\frac{E^2}{4} - FH} t \right) \\
+ \frac{(I - F C_{20} - (E C_{10}/2))}{\sqrt{(E^2/4) - FH}} \exp \left( -\frac{E}{2} t \right) \\
\times \sinh \left( \sqrt{\frac{E^2}{4} - FH} t \right)
\]  

(18)

\[
C_2 = \frac{I}{F} + \left( \frac{C_{20} - I}{F} \right) \exp \left( -\frac{E}{2} t \right) \cosh \left( \sqrt{\frac{E^2}{4} - FH} t \right) \\
+ \frac{(C_{10} H + (C_{20} E/2) - (1E/2F))}{\sqrt{(E^2/4) - FH}} \exp \left( -\frac{E}{2} t \right) \\
\times \sinh \left( \sqrt{\frac{E^2}{4} - FH} t \right)
\]  

(19)

(b) Desorption process (\( C_{B0} = 0 \))

Eqs. (18) and (19) can be further simplified when the desorption process starts by letting \( I = 0 = F, I/F = C_{A0}, \) and \( E = k_d + k' \) (because of \( C_{B0} = 0 \)). One obtains

\[
C_1 = C_{10} \exp \left[ - (k_d + k') t \right]
\]  

(20)

\[
C_2 = C_{20} + \frac{k' C_{10}}{k_d + k'} \left[ 1 - \exp \left[ - (k_d + k') t \right] \right]
\]  

(21)

The totally reversible case is obtained by letting \( k' \) (or \( H \)) = 0, \( C_2 = 0, C_{20} = 0, E = k_d C_{B0} + k_d \). Eqs. (18) and (20) can be reduced to

\[
C_1 = \frac{I}{E} + \left( C_{10} - \frac{I}{E} \right) \exp(-Et)
\]  

(22)

\[
C_1 = C_{10} \exp[-k_d t]
\]  

(23)

3.3. Results and data fitting

Both the experimental conductance transient and the fitted conductance transient, along with the fitted parameters, are shown in Fig. 7. Where \( C_{A10} \) is set to be 100 (real value is unknown); \( P = 0.0312 \), which is the proportional constant discussed in Eq. (12). The obtained fitting parameters are: \( k_d = 1.0 \times 10^{-5}, k_d = 7.5 \times 10^{-3}, k' = 2.0 \times 10^{-4} \), the competition factor, \( f_c \), is 37.5, the range at which the competition of reaction and desorption does exist. It should be noticed that each adsorption/desorption step (every 10 min each step in Fig. 7) is fitted separately using the same set of \( k_d, k_d, \) and \( k' \). That is, the value of \( C_1 (C_{A_1-B_1}) \) and \( C_2 (C_{A_2-B}) \) at the end of one section are the “initial” values (\( C_{10} \) or \( C_{20} \)) for the next step. The values of \( C_1 \) and \( C_2 \) for the first step (2% \( O_2 \) adsorption) are set to be zero.

The model prediction fits the experimental data very well when operating under a lower concentration of \( O_2 \). The deviation begins to enlarge when the \( O_2 \) concentration is higher than 8%. Taking the final run (21% \( O_2 \)) as an example, the actually reacted amount is represented by segment \( \gamma \) in Fig. 7, however, the predicted value from the model is indicated by segment \( \gamma \). On the other hand, the actually adsorbed amount is indicated by segment \( \beta \), while the prediction from the model is segment \( \delta \).

It can be found that the experimental amounts for both adsorption and reaction are deviated from the model prediction at a higher \( O_2 \) concentration, especially noticeable for the adsorption process. It is possible that the numbers of adsorbing site are insufficient for further adsorption when exposed to a higher concentration of \( O_2 \). Smaller deviation is observed for the reaction process involves, and the actual amount of reaction is smaller than that of the predicted one (\( \alpha < \gamma \)), which can be explained by the modified tarnishing film model proposed in our previous work [9]. Since the reacted films are porous and the diffusion (or penetration) is dominant, as shown in Fig. 8, assumption (i) is no longer applied, thus explaining the deviation.

4. Conclusions

In this work, the irreversible behavior observed in \( NO_2 \) sensing with a vacuum evaporated TTF–TCNQ thin film is characterized and modelled. Both conductance and mass transients suggest the irreversibility has something to do with \( NO_2 \) immobilization. With the estimated diameters of gas molecules based on the kinetic theory of gas, the \( NO_2 \) most likely reacts with the complex before diffusing through the film is proposed. According to UV–vis and IR spectra data, as well as information from literatures, a net equation is proposed. In addition, XRD intensity, decreasing after \( NO_2 \) exposure, helps to explain the ongoing reaction that destroyed the crystal packing of the complex. Among all information available, we proposed a hypothetical
mechanism to realize the interaction between the NO₂ gas and the TTF–TCNQ complex. Coincident SEM surface images also support this mechanism.

Moreover, a general model which is suitable to explain three most common phenomena (reversible, partially irreversible, and totally irreversible) is proposed. The sensing of O₂ clearly follows the partially irreversible competition case with a competition factor, \( f_C = 37.5 \). The model fits the experimental data reasonably well at a lower O₂ concentration region, however, the deviation is noticeable at a higher O₂ concentration in which the thermal dynamic equilibrium and gas diffusion take place.

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**References**


**Biographies**

Jung-Yu Liao received his BS and PhD degrees in chemical engineering from National Taiwan University, Taipei, Taiwan, in 1999 and 2004, respectively. His research interest surrounds thin film process in general and gas sensors in particular. Currently, he is a researcher working on organic light emitting diodes (OLED) at the National Taiwan University. In 2006, he moved to the Department of Chemical Engineering at National Taiwan University, currently, he is a Professor jointly appointed by the Department of Chemical Engineering and Institute of Polymer Science and Engineering at National Taiwan University.